VIA FACSIMILE NO. (703) 872-9310

PATENT MIC04 P-106

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Examiner

G. Goudreau

Group

1763

Applicant

Imad Mahawili, PhD

Serial No. Filed

09/488,309

For

January 20, 2000

REACTOR WITH REMOTE PLASMA SYSTEM AND

METHOD OF PROCESSING A SEMICONDUCTOR SUBSTRATE

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

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Catherine S. Collins

Van Dyke, Gardner, Linn & Burkhart, LLP

P.O. Box 888695

Grand Rapids, MI 49588-8695

(616) 975-5500

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PATENT MIC04 P-106

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Examiner

George A. Goudreau

Group

1763

Confirmation No.

4253

Applicant

Imad Mahawili, PhD

Serial No.

09/488,309

Filed

January 20, 2000

For

REACTOR WITH REMOTE PLASMA SYSTEM AND

METHOD OF PROCESSING A SEMICONDUCTOR

SUBSTRATE

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

RESPONSE

In response to the Office Action mailed December 4, 2002, having a three-month period of response ending March 4, 2003, Applicant wishes to amend his application as follows:

IN THE CLAIMS:

Please amend Claim 20 as follows:



20. (Amended) The reactor according to Claim 22, wherein said gas injector comprises an elongate tube with a plurality of orifices through which the gas is injected into said processing chamber.

REMARKS

Applicant has reviewed the Office Action and gratefully acknowledges the Examiner's indication of allowable subject matter. The amendments and remarks presented herein are fully supported by the application as originally filed. No new matter has been added.